

Title (en)
LOW-PARTICLE GAS ENCLOSURE SYSTEMS AND METHODS

Title (de)
GEHÄUSESYSTEME UND -VERFAHREN FÜR PARTIKELARMES GAS

Title (fr)
SYSTÈMES ET PROCÉDÉS D'ENCEINTE À GAZ À FAIBLE TAUX DE PARTICULES

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Application
EP 14810543 A 20140512

Priority

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- US 201414205340 A 20140311
- US 201461983417 P 20140423
- US 2014037722 W 20140512

Abstract (en)
[origin: WO2014200642A1] The present teachings relate to various embodiments of a gas enclosure system that can have various components comprising a particle control system that can provide a low-particle zone proximal to a substrate. Various components of a particle control system can include a gas circulation and filtration system, a low-particle-generating motion system for moving a printhead assembly relative to a substrate, a service bundle housing exhaust system, and a printhead assembly exhaust system. In addition to maintaining substantially low levels for each species of various reactive species, including various reactive atmospheric gases, such as water vapor and oxygen, for various embodiments of a gas enclosure system that have a particle control system, an on-substrate particle specification can be readily met. Accordingly, processing of various substrates in an inert, low-particle gas environment according to systems and methods of the present teachings can have substantially lower manufacturing defects.

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Citation (search report)

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